CLAIMS

1. An alloy consisting of:

at least one selected from Co and Fe; B; C; and the balance being unavoidable impurities,

wherein:

a concentration of C in the alloy is 50 mass ppm or more and 950 mass ppm or less; and

assuming that a total number of Co, Fe and B atoms in the alloy is 100, a composition of Co, Fe and B, excluding C and the unavoidable impurities, in the alloy is represented by the general formula:

$(Co_X - Fe_{100-X})_{100-Y} - B_Y$

wherein X is 0 or more and 100 or less, and Y is 10 or more and 65 or less.

2. An alloy consisting of:

at least one selected from Co and Fe; B; C; an additional metal element M; and the balance being unavoidable impurities,

wherein:

a concentration of C in the alloy is 50 mass ppm or more and 950 mass ppm or less;

assuming that a total number of Co, Fe, B and M atoms in the alloy is 100, a composition of Co, Fe, B and M, excluding C and the unavoidable impurities, in the alloy is represented by the general formula:

$(Co_X - Fe_{100-X})_{100-Y-Z} - B_Y - M_Z$

wherein X is 0 or more and 100 or less, Y is 10 or more and 65 or less, and Z is 0.5 or more and 30 or less; and

the metal element M consists of one or more selected from the group consisting of Ti, Zr, Hf, V, Nb, Ta, Cr, Mo, W, Mn, Re, Ru, Rh, Ir, Ni, Pd, Pt, Cu and Ag.

3. A sputtering target material obtained by using the alloy according to claim 1 or 2.